



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/536,037
Confirmation No. 6381
Filing Date March 27, 2000
Inventor Li et al.
Assignee Micron Technology, Inc.
Group Art Unit 2822
Examiner Toniae M. Thomas
Attorney's Docket No. MI22-1398
Customer No. 021567
Title: Low k Interlevel Dielectric Layer Fabrication Methods

PRELIMINARY AMENDMENT TO ACCOMPANY RCE FILING

To: Mail Stop RCE
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

VIA EXPRESS MAIL

From: James E. Lake (Tel. 509-624-4276; Fax 509-838-3424)
Wells St. John P.S.
601 West First Avenue, Suite 1300
Spokane, WA 99201-3828

REMARKS

This Request for Continued Examination is submitted in an abundance of caution simply to place certain references before the Examiner for consideration. The references are referred to in the Information Disclosure Statement presented herewith.

No new matter is being presented in this application.

This application is believed to be in immediate condition for allowance, and action to that end is requested.

EL979954377